

DUAL ENERGY TRANSPORT MODEL FOR ADVANCED DEVICE SIMULATION

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Abstract

Dual energy transport (DUET) model in semiconductor devices including heterostructures has been developed to simulate the distribution of carrier and lattice temperatures in addition to profiles of the electrostatic potential and carrier concentrations. The modeling approach is in consistency with the conventional drift-diffusion (DD) model, making it easy to implement in the existing code. Carrier energy dependent mobility and impact ionization models have been examined and are used for simulation of various velocity overshoot and hot electron effects. Two simulation examples, one for the submicron MOSFET and another for the deep-submicron SOI, are presented through comparison with measurement data to demonstrate the improvement of the new model over DD model in predicting the device characteristics for modern (submicron) structures.

I INTRODUCTION

As the feature size of semiconductor devices shrinks to the quarter-micron regime, nonlocal effects such as hot electrons and velocity overshoot become important in determining the device characteristics. The conventional drift-diffusion transport model has been and continuously been used in industry and academia for design and analysis of IC devices largely because its auxiliary physical models such as the field-dependent mobility model and impact ionization model are well calibrated. But it fails to predict those device characteristics which becomes critical in sub- and deep sub-micron devices. A notable example is the substrate current in MOSFET. Neither can DD model provide such vital information as to the average kinetic energy of carriers in the device. On the other hand, Monte Carlo (MC) method can provide very detailed information about the carrier distribution in real and momentum spaces. But in addition to the excessive CPU time requirement and complexity of model parameters, most present MC codes can only simulate one-carrier device behavior, thus are not yet suitable for the design of practical devices. Through tracing back to the origin of DD model from Boltzmann Transport Equation (BTE) and by relieving the constraints of constant effective mass and temperature, we were able to develop a more complete transport model in semiconductors, which reveals not only the carrier concentration and current density (essentially a measure of carrier average velocity) but also the carrier energy density. Assuming Fermi-Dirac (FD) statistics as the basis for the distribution function and applying the perturbation theory, the average kinetic energy can be linked to the temperature parameter used in FD statistics in the same formulation as for an ideal gas in classical thermodynamics, thus correctly identifying the

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